



Docket No. 740756-1799

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT application of )

Mitsunori SAKAMA )

Serial No. 09/070,908 )

Filed: May 4, 1998 )

For: FILM FORMING METHOD AND )

FILM FORMING APPARATUS )

Art Unit: 1762

Examiner: M. Padgett

#226  
6/20/01

AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Responsive to the Office Action dated **February 15, 2001**, the period for response having been extended **one (1) month to June 15, 2001**, the following amendments and remarks are submitted in connection with the above-identified application.

In the claims:

Please amend the claims as follows. Attached hereto is a marked-up copy of the amended claims.

23. (Amended) A film forming method comprising the steps of:
- supplying hydrogen gas into a chamber;
  - supplying radio frequency energy in said chamber to generate plasma from said hydrogen gas by radio frequency discharge;
  - supplying a reactive gas into said chamber at a same flow rate as supplying said hydrogen gas; and
  - forming a semiconductor film over a substrate in said chamber by decomposing said reactive gas using said radio frequency energy,

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